



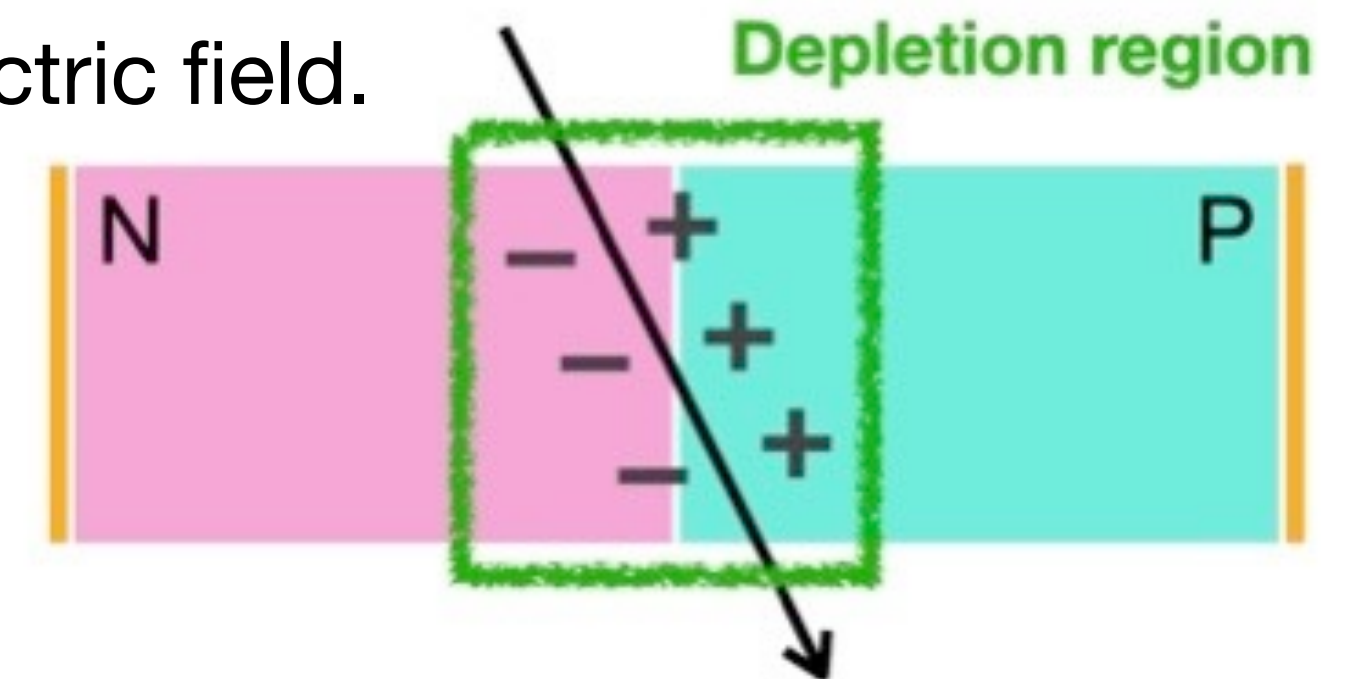
Fast simulation of the Silicon Pad Detector

JaeYoon CHO
INHA University

CENUM Workshop
04th July 2020

Silicon Detector

- Because of its superior energy resolution and good response time, Silicon detector is widely used in nuclear physics experiments.
- The region where any free charge carrier (electrons and holes) rarely exists is called the **depletion region**.
- When the charged particles pass through the depletion region, they lose their energy by creating electron-hole pairs along the trajectory.
- Created electrons and holes are drifted to the electrodes because of the external electric field.
- To increase the depletion region, a reverse-bias voltage is applied to the device.

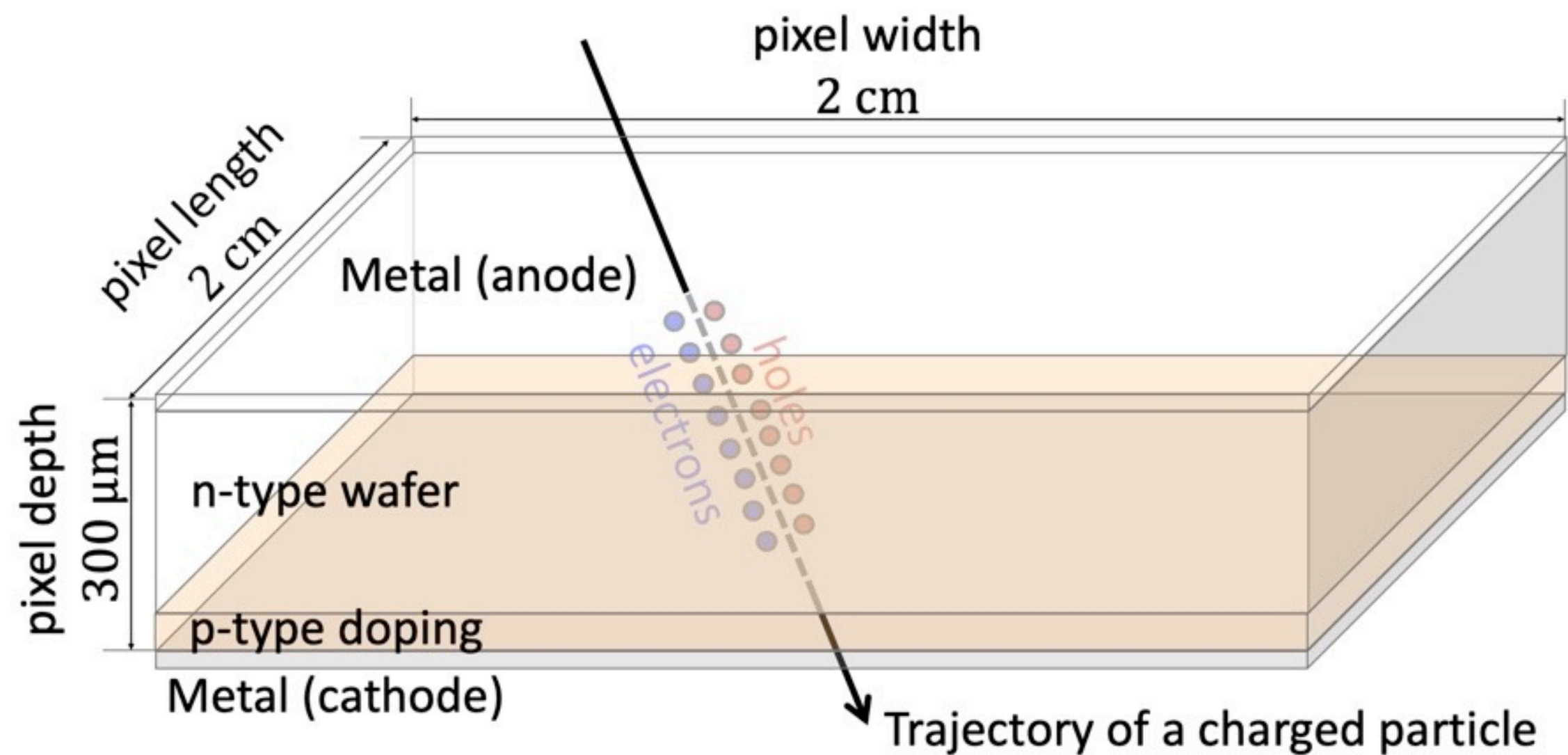


Detector Simulation

- We introduce an **open-source**-silicon-detector simulator named "***Fast Silicon Simulation***".
- Calculated results by "***Fast Silicon Simulation***" is compared with the results by a commercial simulation.

Simulation Setup

- We construct a 2cmx2cmx300μm volume of device composed of lightly doped n-type bulk and heavily doped p-type pad.
- To simplify electron-hole-pair generation process, we consider the MIP(Minimum Ionizing Particles).



Input parameter		
Size(width × length × depth)	2cm × 2cm × 300μm	
Reverse bias voltage	140V(fully depleted)	
Operation temperature	300K	
Doping density	n-type	$1.9 \times 10^{18} \text{ m}^{-3}$
	p-type	10^{21} m^{-3}
Mobility	Electron	$0.135 \text{ m}^2\text{V}^{-1}\text{s}^{-1}$
	Hole	$0.048 \text{ m}^2\text{V}^{-1}\text{s}^{-1}$

Incident beam and its energy loss	
Density	$75\mu\text{m}^{-1}$ (MIP)
Angle of incidence	0 degree(vertically incidence)
Position	$(0,0,0) \rightarrow (0,0,300)$

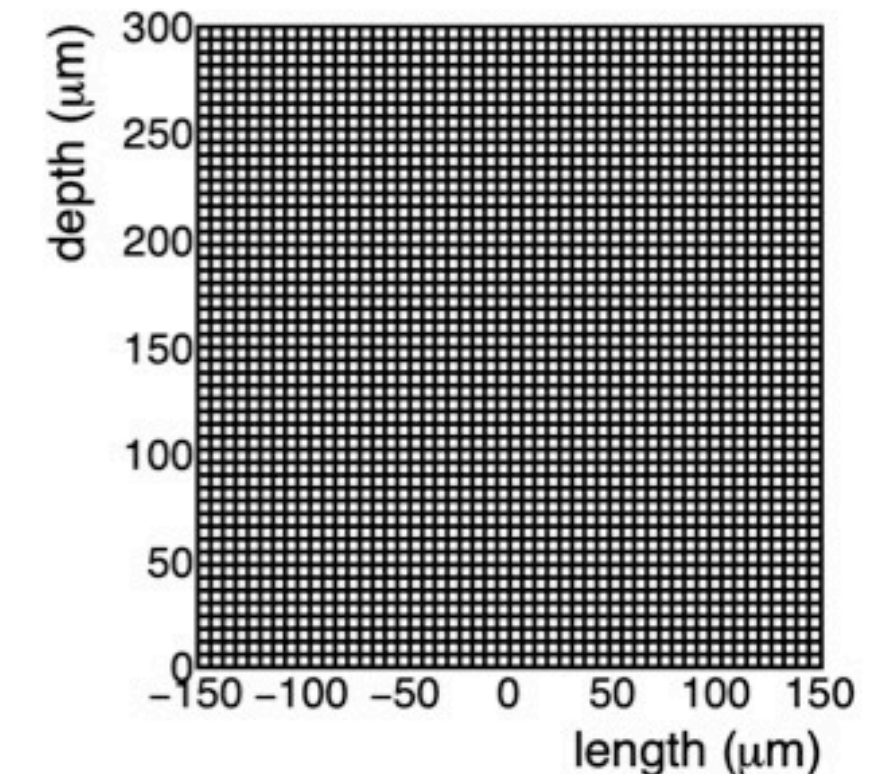
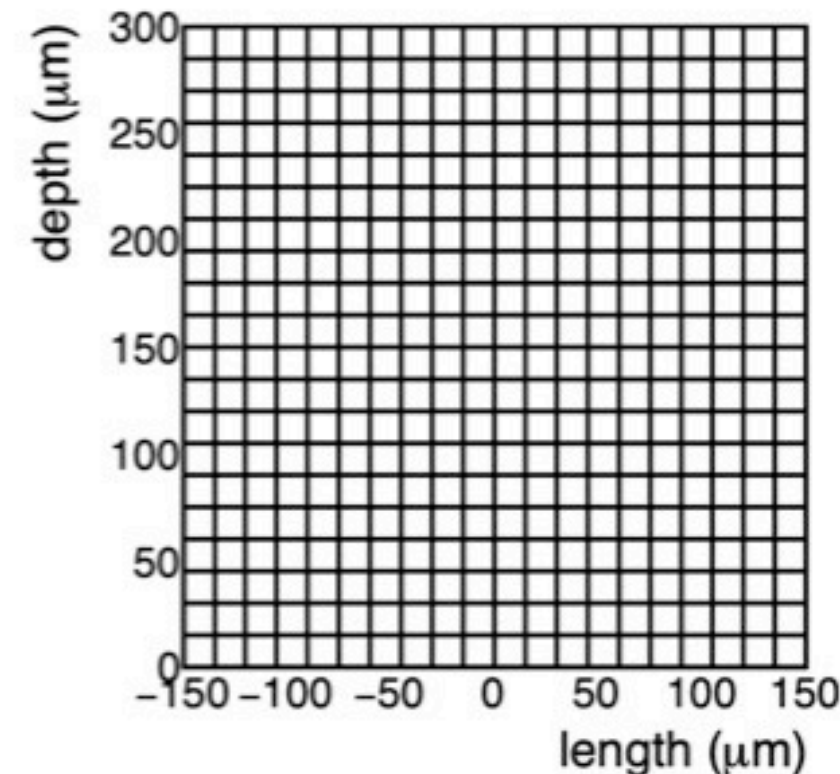
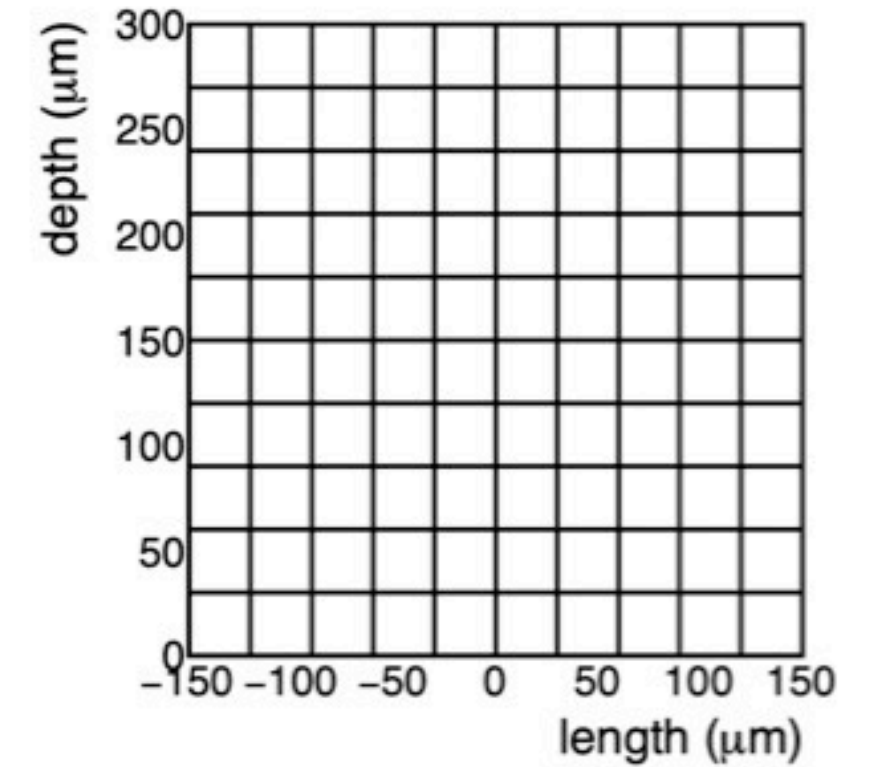
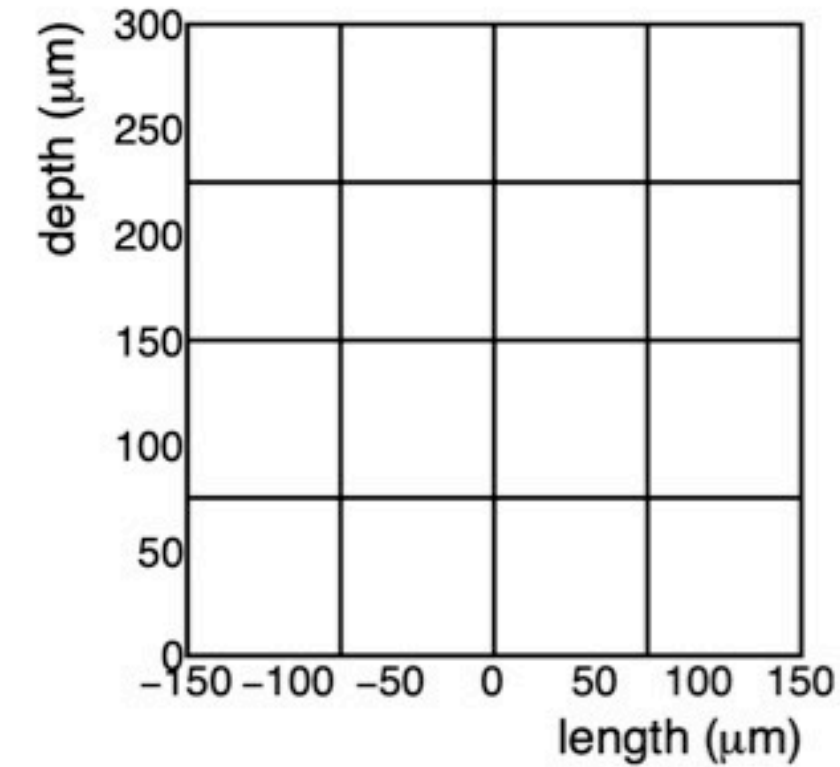
Electric potential $\nabla^2 \phi = -\frac{\rho}{\epsilon}$

where ϕ : electric potential, ρ : volume density, ϵ : permittivity of the material

In this study, electric potential is calculated by the *Multi-grid method*.

Multi-grid method

- Apply the iteration method to wider lattices as an initial condition.
- By interpolating with the values of the surrounding lattice components, the denser lattices are created.
- For each step, the iteration method is repeated until the potential values at the lattices do not change by less than 0.01%.
- By filling the inside of the grid with the average value, calculation time can be reduced.



When the potential is calculated, other quantities are calculated by following the equations below.

Electric field $\vec{E} = -\nabla\phi$

Induced current for electron $\vec{J}_e = e\rho_e\mu_e\vec{E} + eD_e\nabla n_e$

And hole $\vec{J}_h = e\rho_h\mu_h\vec{E} - eD_h\nabla n_h$

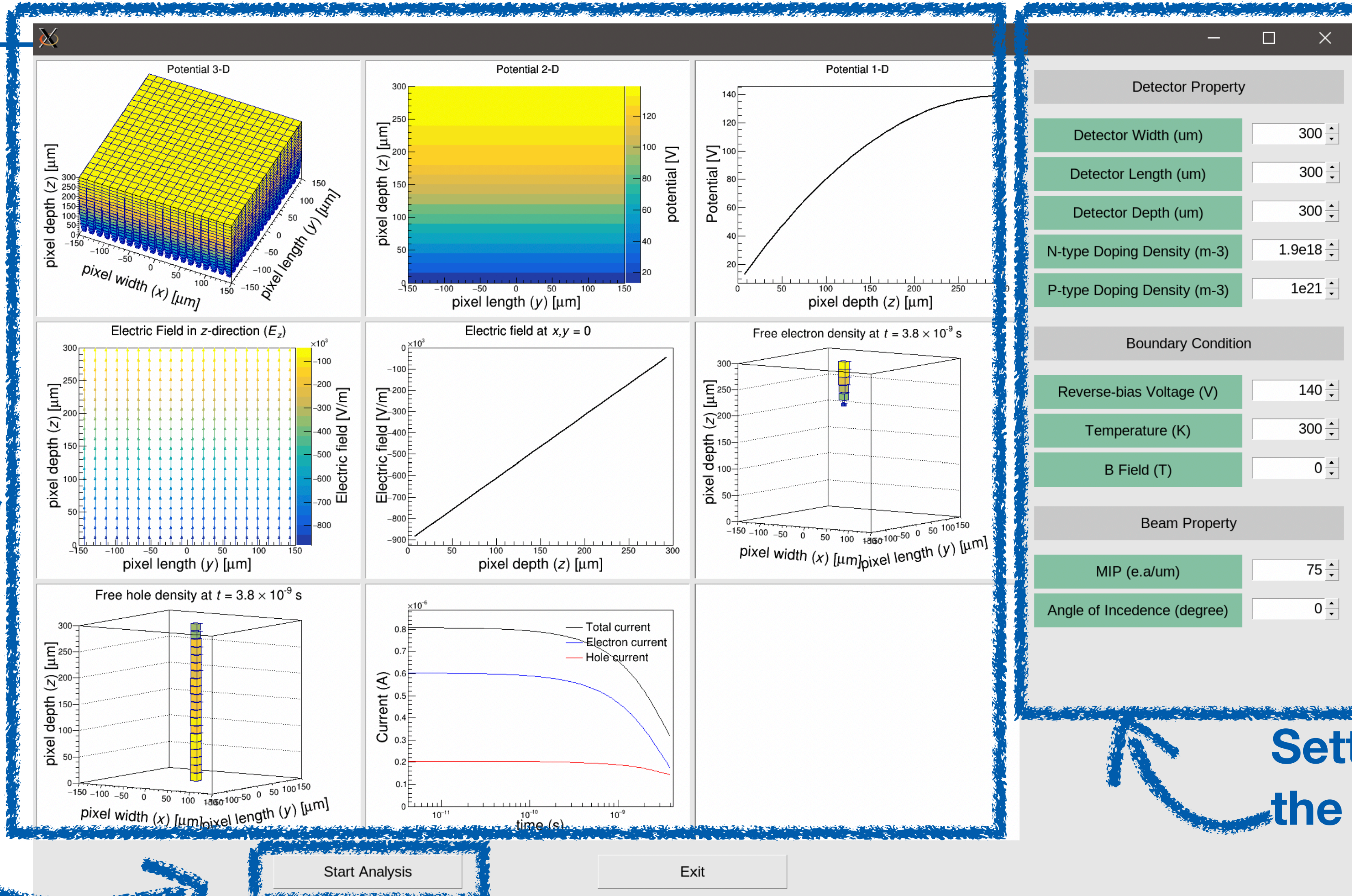
where $\vec{J}_e(\vec{J}_h)$: current density of electron(hole), $\rho_e(\rho_h)$: volume charge density of electron(hole), e : elementary charge, $n_e(n_h)$: electron(hole) density, Einstein's relation $D_e = -k_B T \mu_e / e$ ($D_h = k_B T \mu_h / e$)

Mobility

$$\mu_e(E) = \mu_{0,e} \left(\frac{1}{1 + \left(\frac{\mu_{0,e} E}{v_{sat,e}} \right)^2} \right)^{1/2} \quad \mu_h(E) = \mu_{0,h} \frac{1}{1 + \frac{\mu_{0,h} E}{v_{sat,h}}}$$

Where $\mu_{0,e}(\mu_{0,h})$: mobility for electron(hole), $v_{sat,e}(v_{sat,h})$: saturation velocity of electron(hole)

Results



The interface displays several simulation results:

- Potential 3-D:** A 3D surface plot of potential vs. pixel width (x) and pixel length (y).
- Potential 2-D:** A 2D heatmap of potential vs. pixel length (y) and pixel depth (z).
- Potential 1-D:** A line graph of potential vs. pixel depth (z).
- Electric Field in z-direction (E_z):** A 2D plot of electric field vs. pixel length (y) and pixel depth (z).
- Electric field at $x, y = 0$:** A line graph of electric field vs. pixel depth (z).
- Free electron density at $t = 3.8 \times 10^{-9}$ s:** A 3D plot of electron density vs. pixel width (x) and pixel length (y).
- Free hole density at $t = 3.8 \times 10^{-9}$ s:** A 3D plot of hole density vs. pixel width (x) and pixel length (y).
- Current vs. time:** A line graph showing Total current, Electron current, and Hole current vs. time (s).

The **Setting the Input Parameter** panel on the right includes:

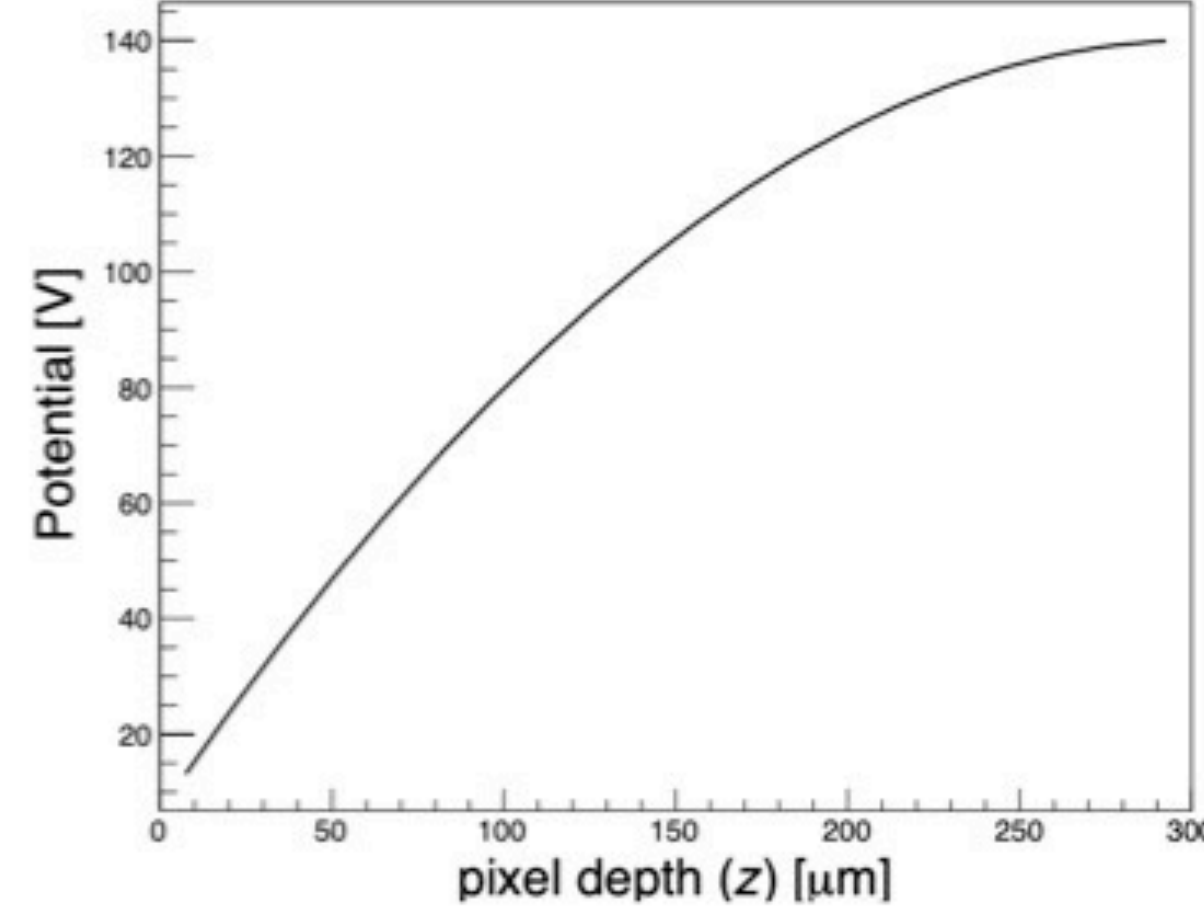
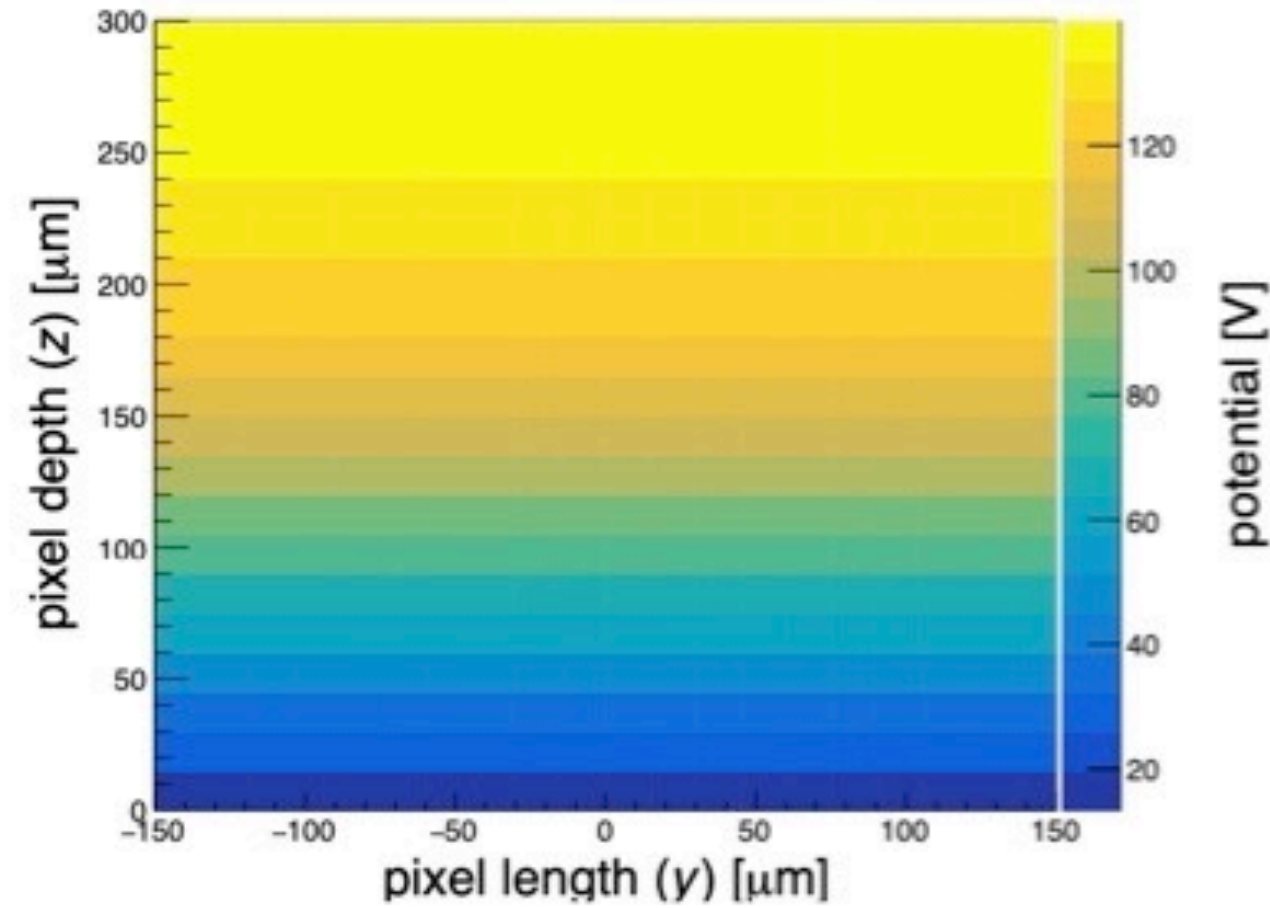
- Detector Property:**
 - Detector Width (um): 300
 - Detector Length (um): 300
 - Detector Depth (um): 300
 - N-type Doping Density (m-3): $1.9e18$
 - P-type Doping Density (m-3): $1e21$
- Boundary Condition:**
 - Reverse-bias Voltage (V): 140
 - Temperature (K): 300
 - B Field (T): 0
- Beam Property:**
 - MIP (e.a/um): 75
 - Angle of Incidence (degree): 0

At the bottom, there are buttons for **Start Analysis** and **Exit**.

Result panel

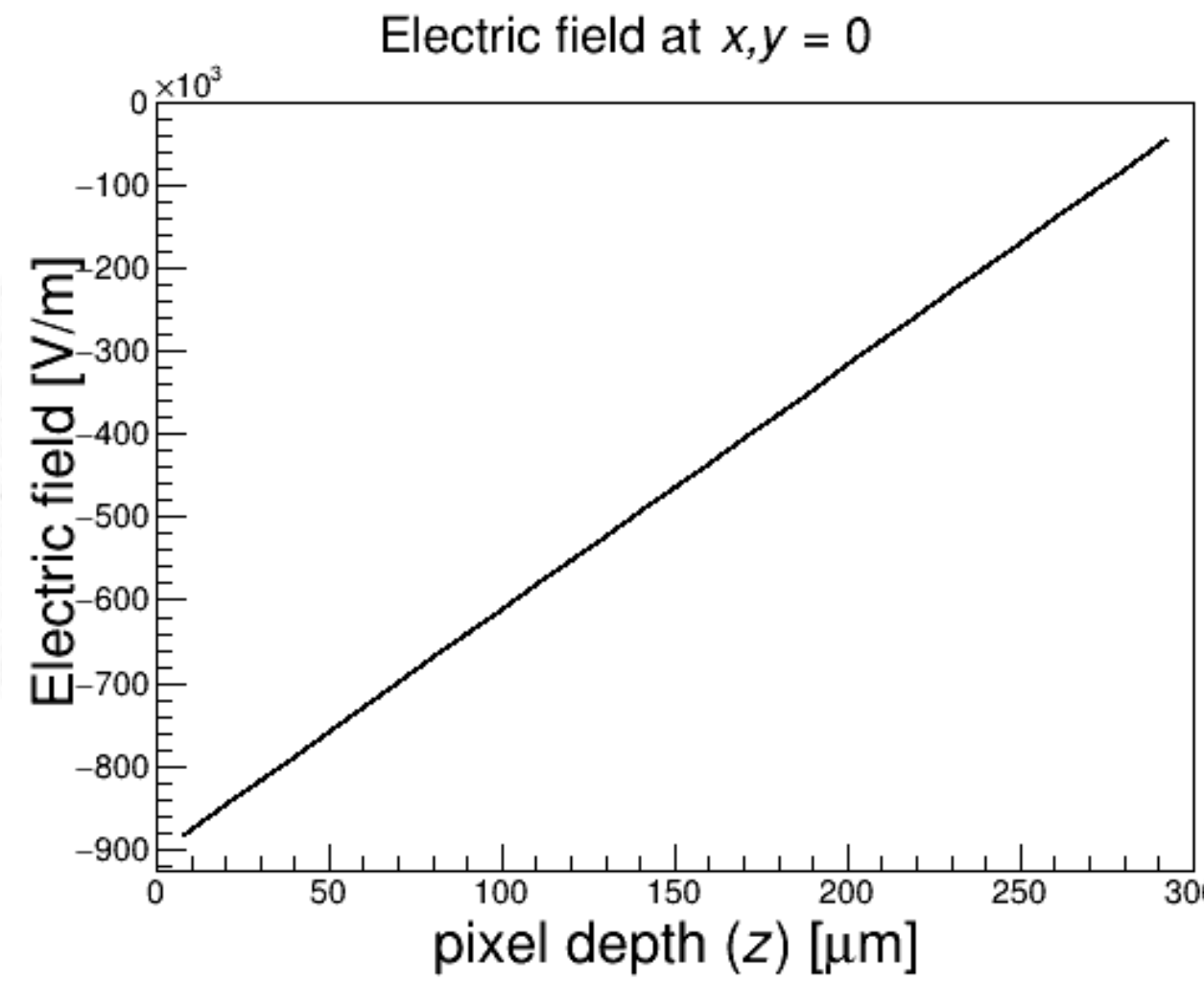
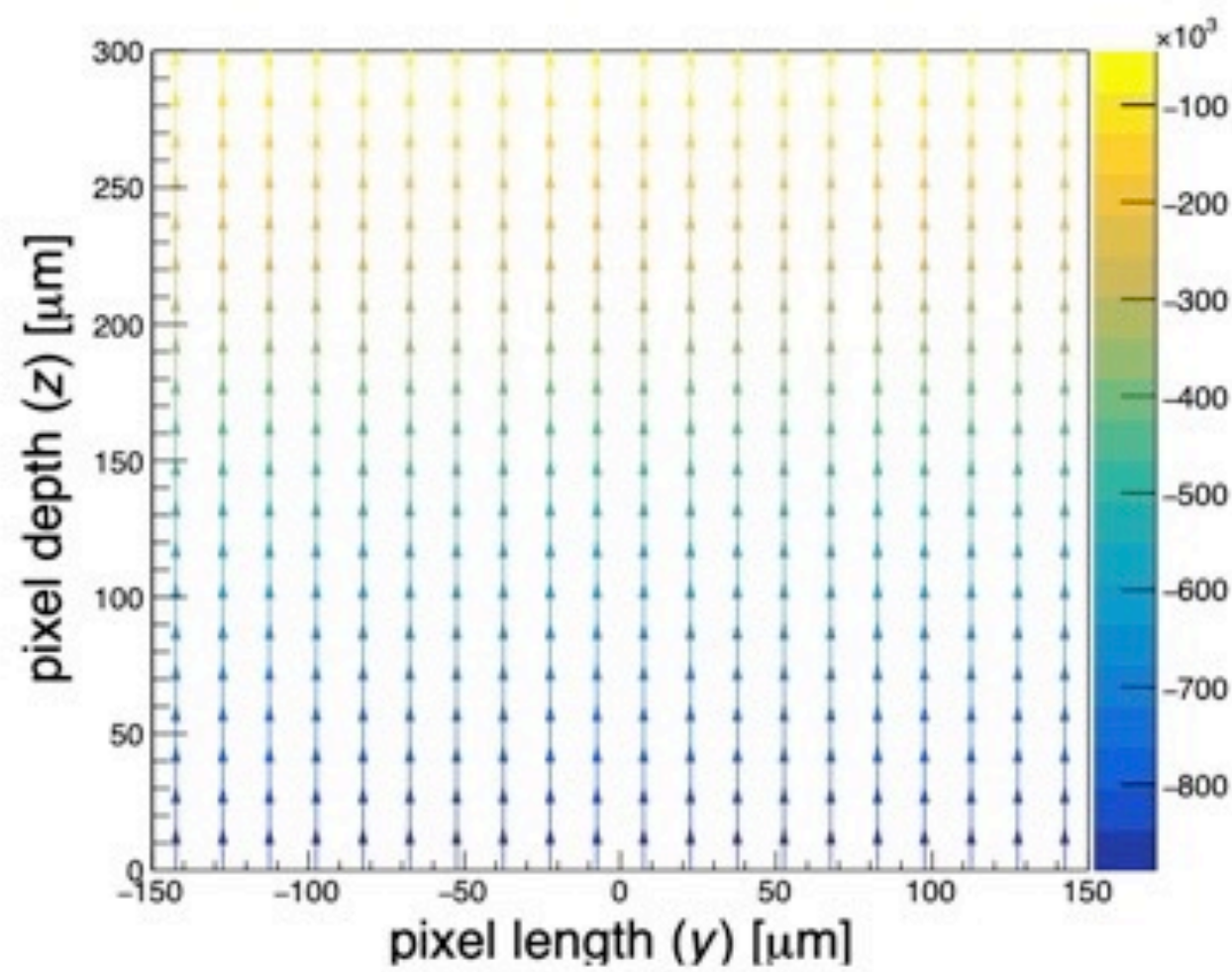
Setting the Input Parameter

Analysis Start!



Potential

- The potential projected in yz -plane at $x = 0$
- The potential distribution along the depth direction of the device in the depleted p-n junction follows the second-order polynomial.

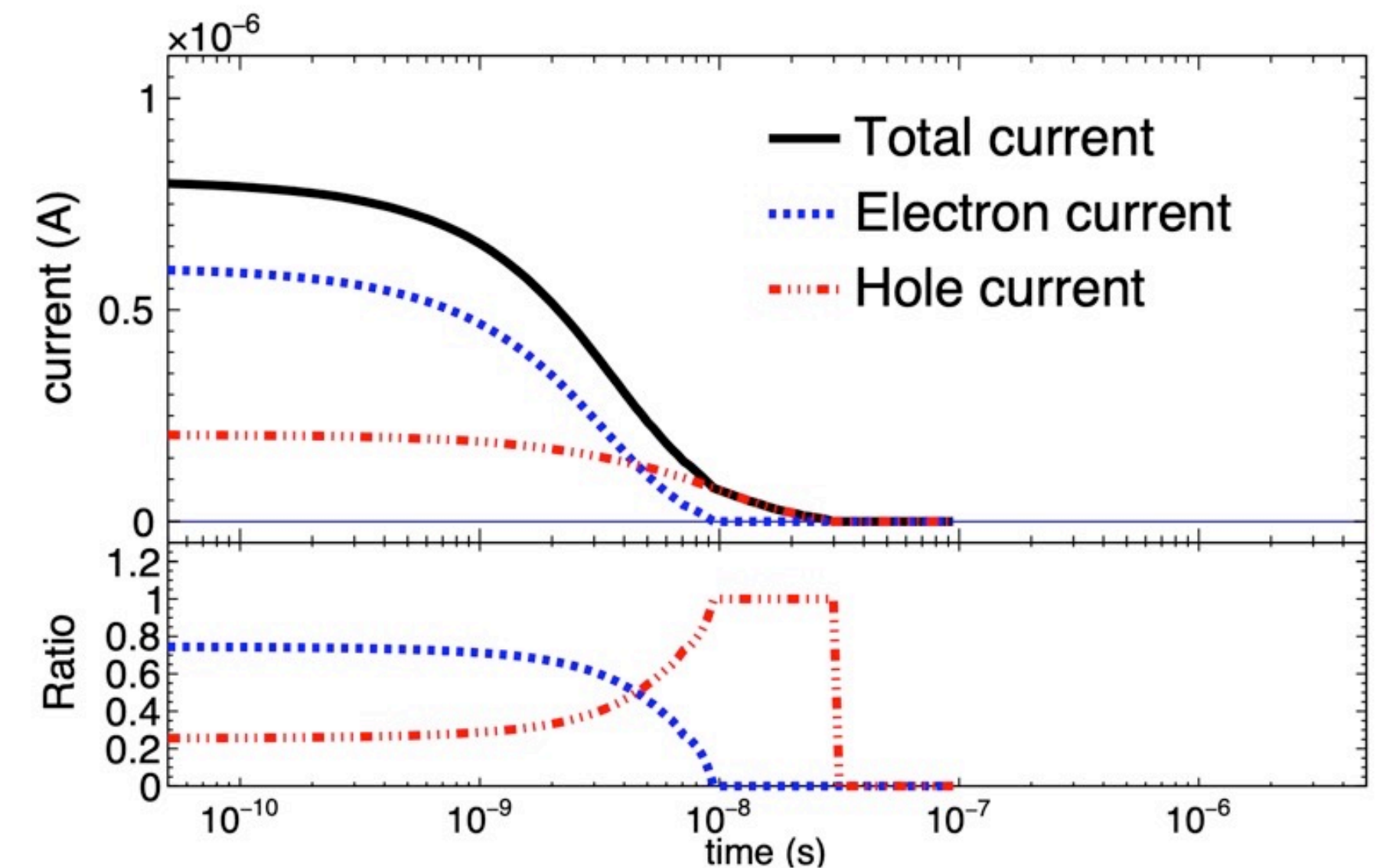
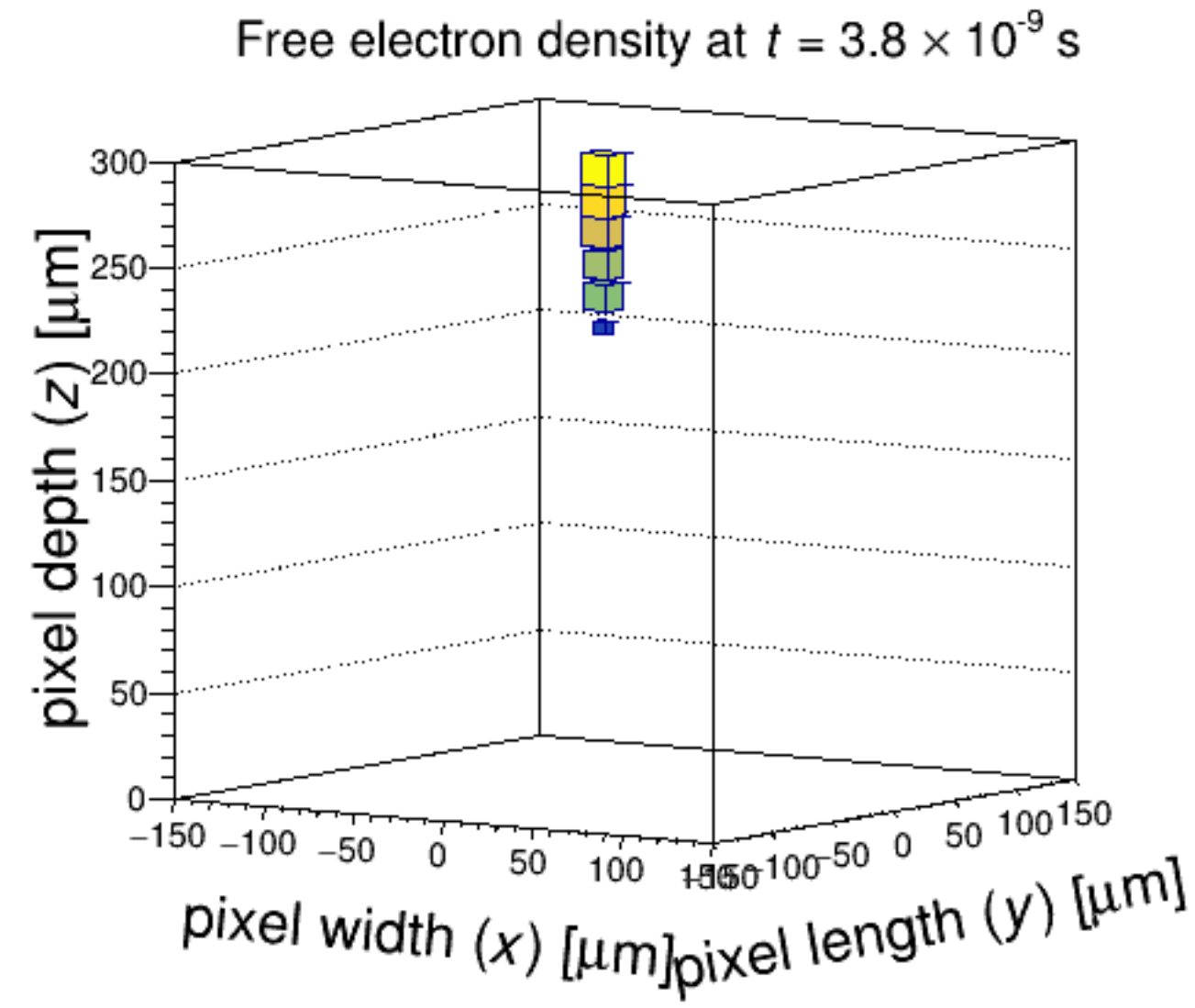
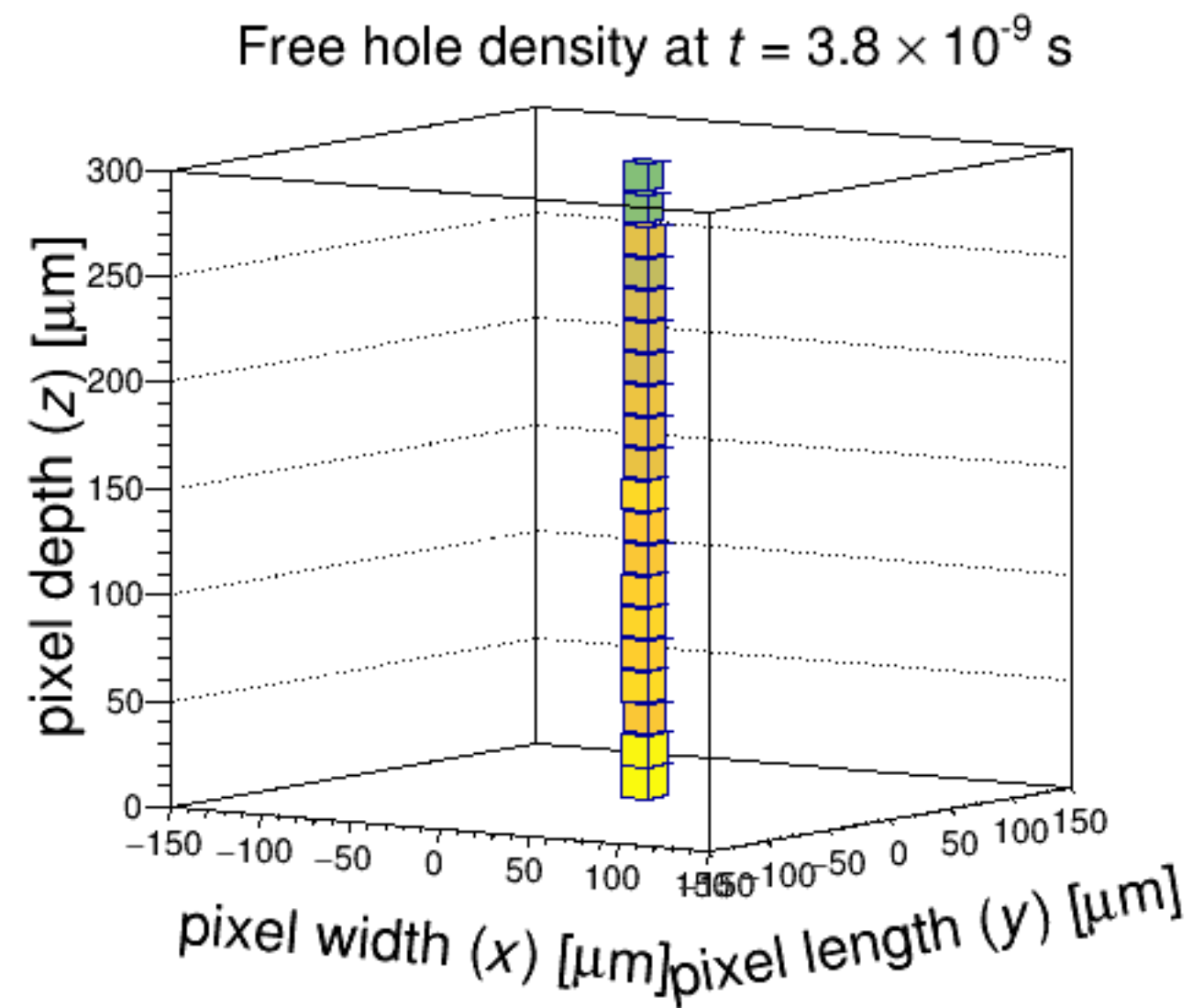


Electric field

- The direction and magnitude of the electric field along the depth axis.
- The electric field varies linearly from top to bottom of the device due to its uniform doping density.

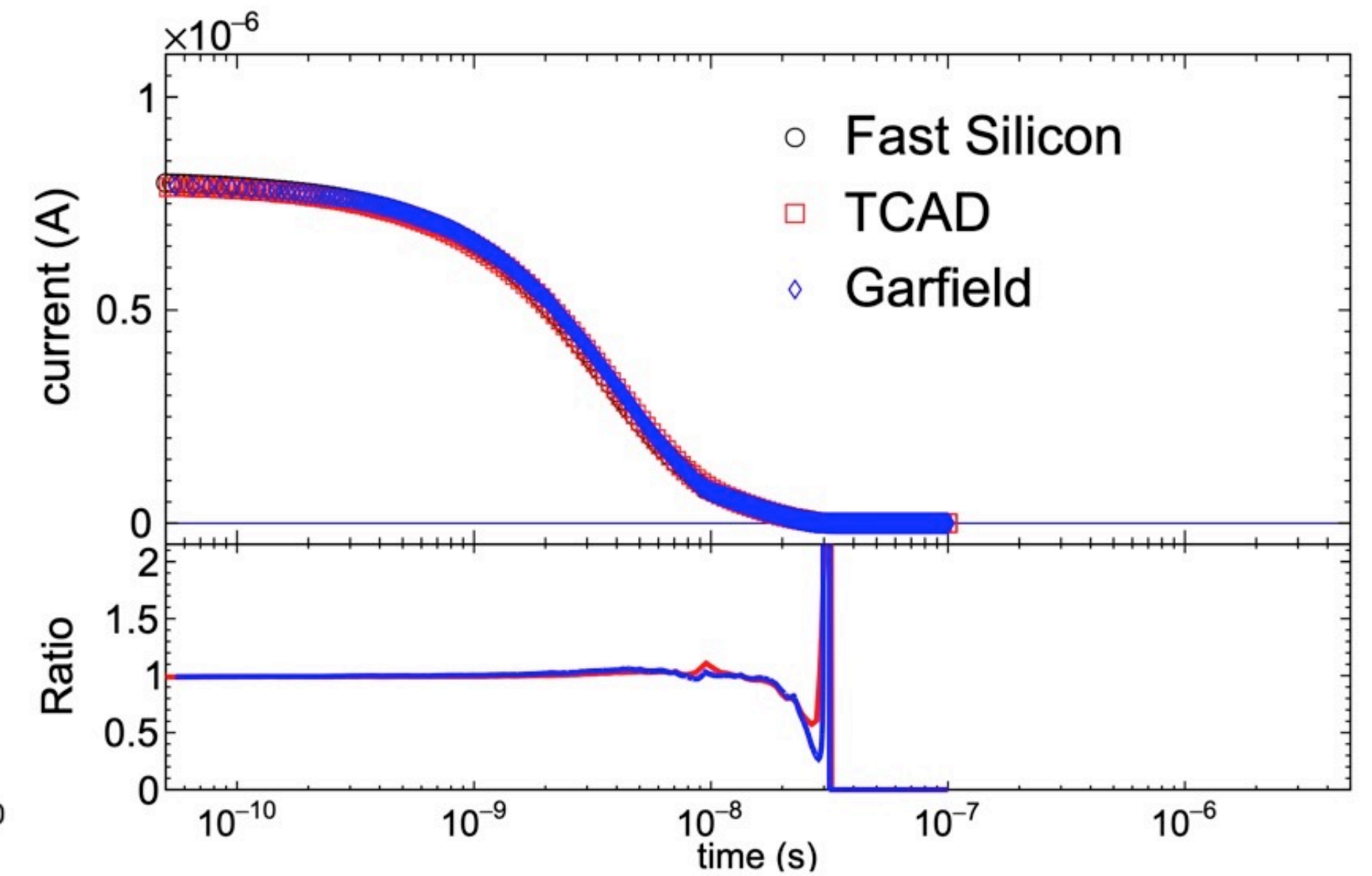
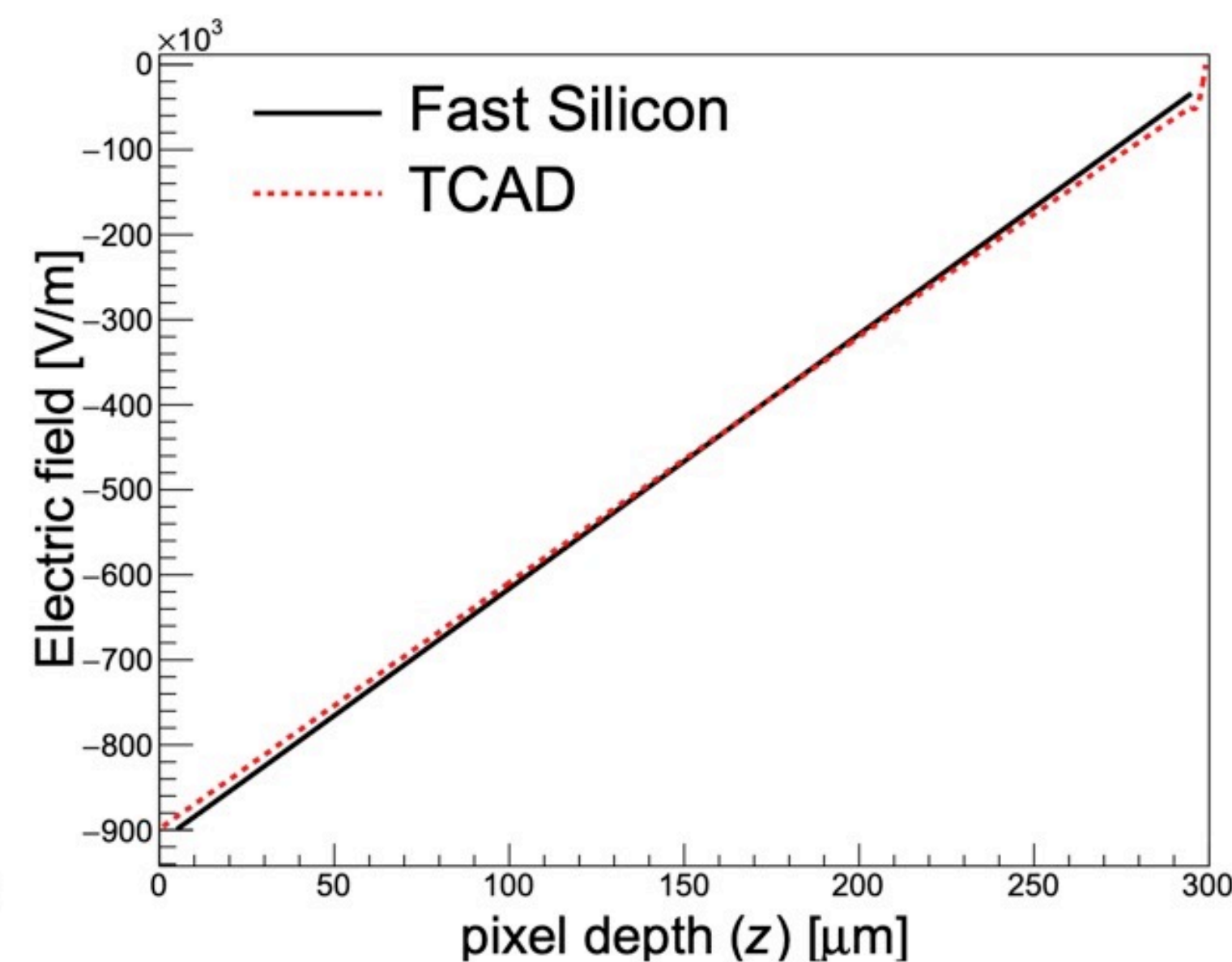
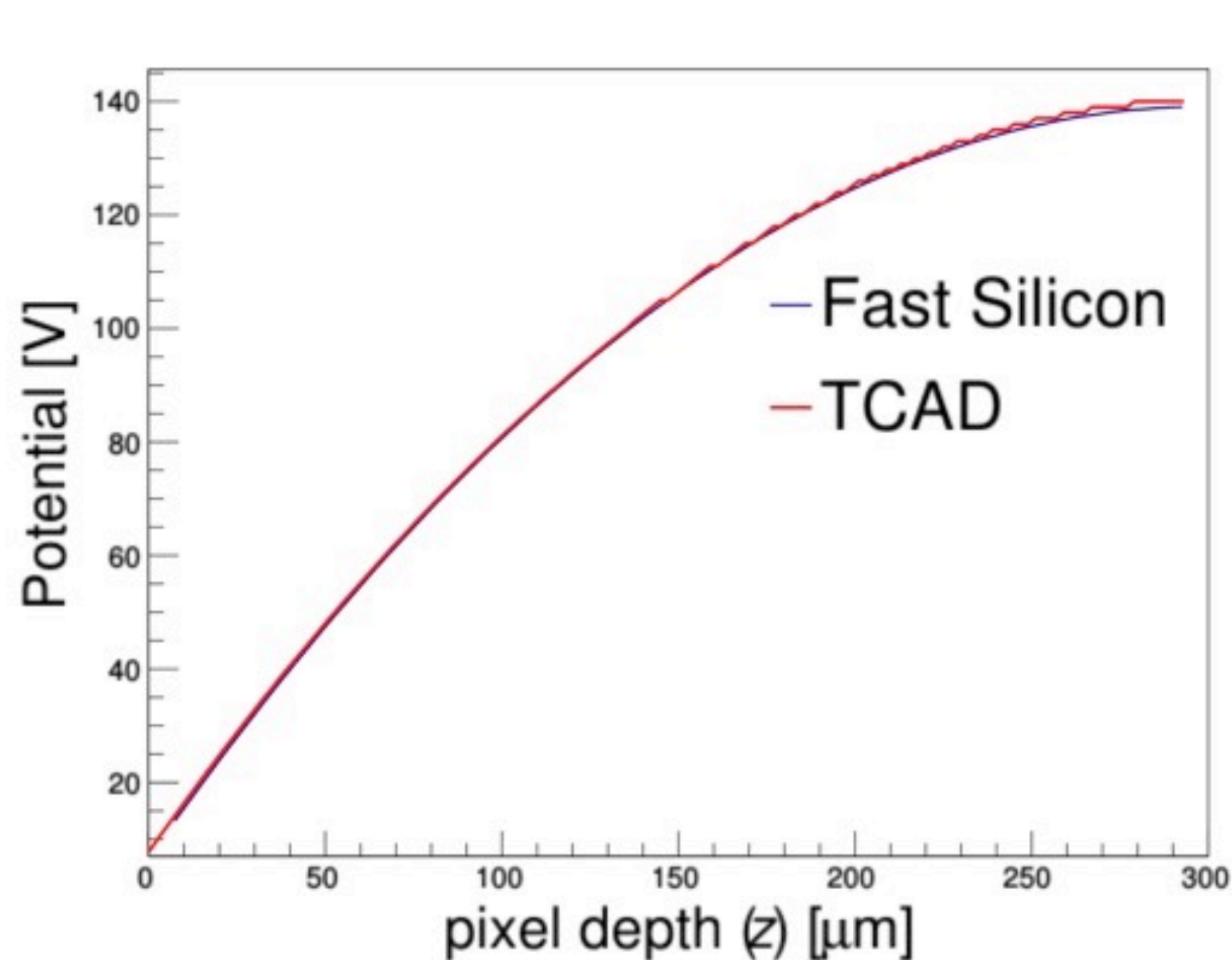
Induced current

- The number of generated electron-hole pairs is set by 75 per μm in the silicon volume.
- Holes move slower than electrons in the device. The hole current is lower and falls later than the electron current.
- Also, electrons are collected quickly to the anode than holes.



Comparison with other simulation

- Silvaco TCAD (Technology Computer-Aided Design) is a commercial semiconductor device simulator.
- Garfield++ is a simulation toolkit for particle detectors based on ionization measurement in gases or semiconductors.
- Electric field, potential, and induced currents in the Fast Silicon Simulation are consistent with the results from TCAD and Garfield++.



Conclusion & Summary



- We introduce a new **open-source**-silicon-detector simulator named "***Fast Silicon Simulation***".
- To calculate the potential and electric field, the multi-grid method and iterative method are used.
- Results by *Fast Silicon Simulation* are consistent to the results by TCAD simulation qualitatively and quantitatively.
- *Fast Silicon Simulation* is **100 times faster** than TCAD simulation.
- This simulation method can be used to study the optimized design and physical properties of the silicon detector.